

Photomask Assembly and Method for Protecting
the Same from Contaminants Generated During
Lithography Process

Inventor(s): Xun Zhang et al.

Page 1 of 2



FIG. 1

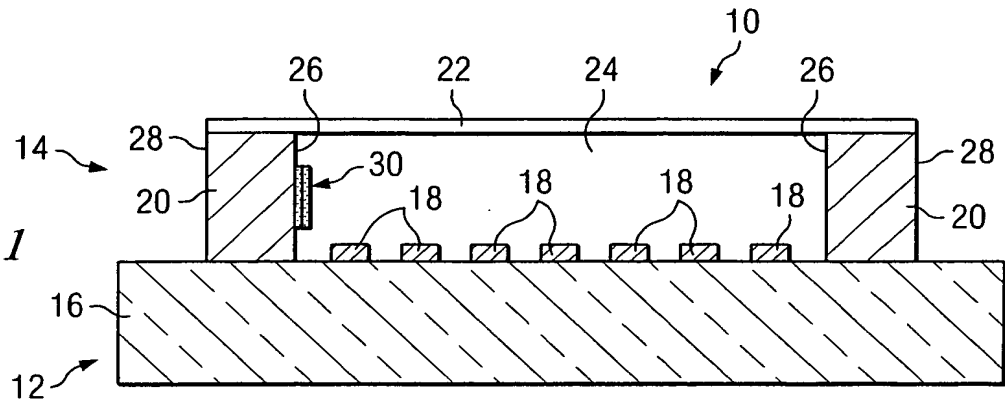


FIG. 2

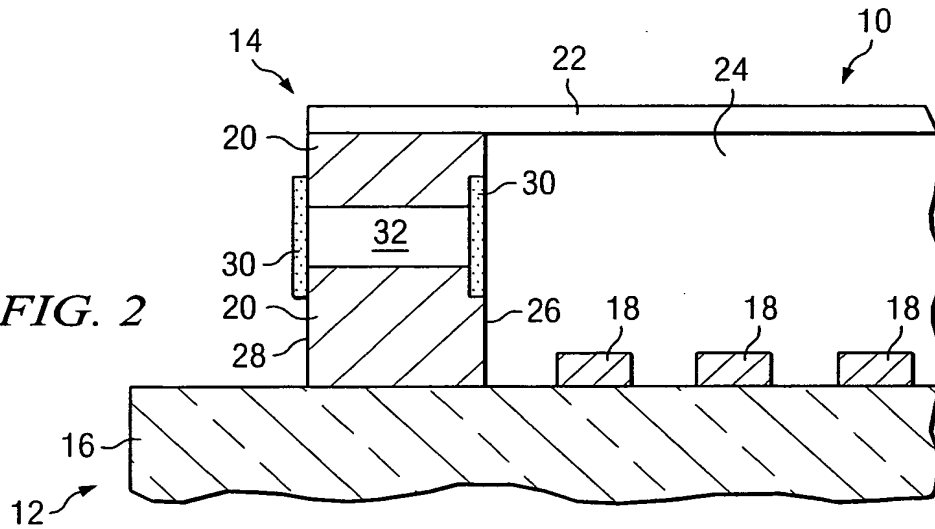


FIG. 3

